Electron microscopy

Most widely used nanoscale microscopy. Based on possibility to create bright electron beam with sub-nm spot size. History: Ernst Ruska (1931), Nobel Prize (1986)

For visible light λ =400-700nm, for electrons de Broglie wavelength

 $\lambda = \frac{h}{\sqrt{meV_0}}$ if $V_0 = 5kV \rightarrow \lambda \approx 0.2$ Å

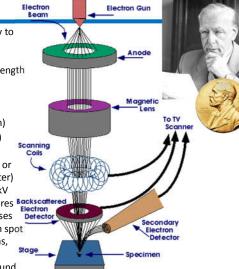
Types

Scanning electron microscopy (SEM) (standard res. 1nm) Transmission e microscopy (TEM) (resolution sub 50pm) The SEM System

Creation of e beam: thermionic emission from a filament or field emission from a sharp tip (cold cathode or heated emitter)

- Acceleration to a desired beam energy from 0.2kV 300kV
- Beam passes through magnetic condensor lenses, apertures Backson in vacuum system and focused by magnetic objective lenses SEM objectives are close to sample → focusing to sub nm spot
- electrons hitting the surface generate secondary electrons, which are detected with (scintillator/photomultiplier) or backscattered electrons are detected with a detector around the electron beam line.
- scanning the surface in x,y direction by scanning coils the secondary/backscattered electron signal is recorded.
- It workes in vacuum, (Special systems also in low vacuum ~mbar →biology) Nanotechnology and material science Lecture V

Nattelson Section 4.1.3



(Right) Ernst Ruska, who received the Nobel Prize 1986 for his fundamental work in electron optics, and for the design of the first electron microscope, (Left) Basic setup of a SEM. Electrons are generated by a gun and accelerated via an anode by dc voltage. The e/beam is focused to small spot size by magnetic lenses, its direction is oriented by scanning coils. The electrons hitting the surface either backscatter or generate secondary electrons, which are detected. https://www.purdue.edu/ehps/rem/rs/sem.htm

Electron microscopy

Beam generation

Thermionic emission gun:

Heated filament coated with a low workfunction material, heated to ~1000K. Electrons are thermally excited out of the metal. They accelerated away by anode with high positive voltage. Current density:

$$J = \frac{4\pi me}{h^3} (k_{\rm B}T)^2 \exp\left(-\frac{\phi}{k_{\rm B}T}\right)$$

Simple, but emitted electrons have a broad energy spectrum. → Role of chromatic aberration

Field emission gun (FEG):

extremely sharp tip to generate very high local

electric fields. Assuming the end of the tip as a sphere with radius a, the electric field at the surface:

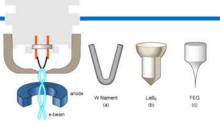
$$E = \frac{1}{4\pi\,\varepsilon_0} \frac{Q}{a^2} = \frac{V}{a}$$

E.g. a=100nm, V=1kV \rightarrow E= 10¹⁰V/m. Thus if φ =2eV the width of tunnel barrier tilted by E is 2Å. Electrons could tunnel through the tilted potential barrier. This is the problem of Fowler-Nordheim tunneling:

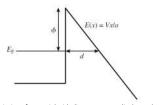
$$J \propto E^2 \exp{-\left(\frac{4\sqrt{2m}}{3e\hbar}\frac{\phi^{3/2}}{E}\right)}$$

Large electron current without heating → monoenergetic e beam. There are cold cathodes or thermally assisted Schottky type.

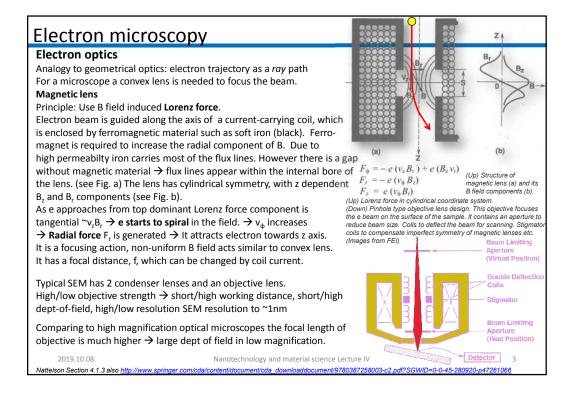
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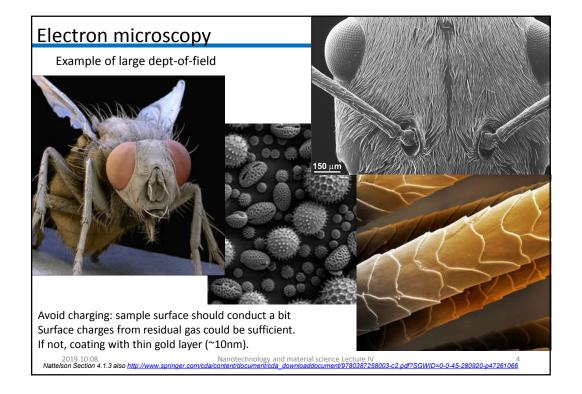


Structure of the gun. A W filament (thermionic emission) or a sharp t (for FEG) is surrounded by the Wehnelt cylinder. The tungsten filament is heated by passing current between its ends. Below the cap sits an anode which, being positive, attracts the electrons away from the filament. http://www.ammrf.org.au/myscope/sem/practice/principles/gun.php



(Up) The variation of potential with distance perpendicular to the surface of a metal. Inside the metal (left) electrons at the Fermi energy are with energy Φ (the work function) below the energy of free electrons. The application of a large electric field, V/a, generates a small tunneling barrier (width d) for electrons at the Fermi energy to escape through





Electron microscopy

SEM

Accelaration voltage (Vacc): 1-30keV

Spatial resolution is limited not by diffraction rather on the achieved spot size (non ideal focusing) and interaction volume.

Advantage: large magnification range (from 10 above 500k) is possible with large dept of field, bulk samples also, analytical techniques to study composition

Detectors

Secondary electron detector (SE):

As electron beam hits the surface and electrons are kicked out from lower shells and detected.

- Heavy elements are more effective at producing secondary electrons. E.g. large contrast of Au on Si.
- From very close to the specimen surface → high resolution image of the surface. Highest resolution: 0.4nm (2009)
- Nice contrast of edges in surface topography due to many escaping electrons
- Higher V_{acc} -> shorter e travel time \rightarrow better resolution, but also deeper penetration

Backscattered electron imaging (BSE): Electrons of the beam reflected elastically. Signal from deeper location → lower spatial resolution. It strongly depend on Z. →Contrast between areas with different composition.

(Right) SEM images of Fe particles in carbon obtained with secondary electrons (left) and back-scattered electrons (right). The BSE image shows the Fe particles with bright contrast, http://www.microscopy.ethz.ch/bse.htm

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(Up) - From left to right: Mechanism of

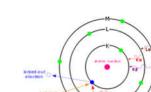
http://www.microscopy.ethz.ch/bse.htm

electrons are generated.

electron generation, electron backscattering and

emission when electrons relax to empty core state (Down) Edge effects: more secondary electron car

leave the sample at edges leading to increased brightness, which helps to get good contrast in surfac topography. Figure also shows the interaction volume where primary electrons penetrate and backscattered



Electron microscopy

SEM

Energy-dispersive X-ray spectroscopy (EDS)

If the incident electron beam has sufficient energy to knock core electrons out of the sample. Higher energy electrons from outer shell fills the hole and the sample then fluoresces in the x-ray, and the resulting radiation is measured by an energy-dispersive spectrometer. It is very useful for elementary analysis.

Each element has a characteristic set of peaks on its electromagnetic emission spectrum, it can be used for analyzing composition of the specimen.

- + Good for fast check of elementary composition. Qualitative composition can be estimated based on peak-height ratios.
- Elements could have overlapping peaks (e.g. Mn-K_α and Cr-K_β, or Ti-K_α)
- Not good for light elements

Electron backscatter diffraction (EBD)

Backscattered electrons which Bragg diffract from the sample. Characterization technique to study any crystalline or polycrystalline material. Revealing texture, defects, grain morphology and deformation.

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(Up) Principle of the underlying process of EDS (Down) EDS spectrum of NIST K309 glass. Silicon, aluminum barium, calcium, iron, and oxygen are identifiable in the spectrum. J. Goldstein, et. Al, Scanning Electron Microscopy

and X-ray Microanalysis, 3rd, Springer, New York (2003).

(Left) Electron backscatter diffraction pattern of monocrystalline silicon, taken at 20 kV with a field-e electron source

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Accelaration voltage (Vacc): 100-300keV

Spatial resolution is \approx 40pm at V_{acc} =200kV in "aberration-corrected" microscopes (spherical aberration is corrected to 5th order). Possible to image lighter atoms like lithium

TEM System

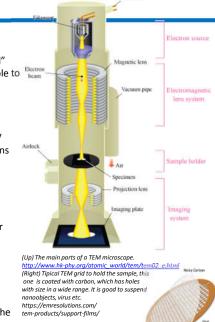
- Thin specimen (~100nm) is placed in the path of the e beam.
- Electrons emitted from the filament are accelerated to ~100keV
- Primary beam formation with condenser lens, then objective lens focus the beam to the sample
- There is interaction with the specimen while electron beam transmit through.
- The projector lens behind the sample expands the beam to the detector (e.g. CCDs).
- Imaging system is e.g. a YAG screen coupled to CCD or phosphor screen.

Specimen stage: Metal grid with a size of ~5 mm, with a thickness and mesh size ranging from a few to 100 μ m.

Limitations of TEM: Fabrication of thin samples is challenging (sometimes invasive). Small field of view. Large e flux can damage the sample.

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Electron microscopy

TEM Imaging modes

For small magnification contrast is due to absorption (thickness, composition) for large ones wave nature of electrons (its phase) dominates.

Bright field imaging Dark regions indicating occlusion (scattering or absorption) of the incident beam. Direct transmitted electrons.

Dark field image Simple transmitted electrons are not detected, but diffracted incident beam is measured. It is powerful to analyze the crystal structures of solids.

At 200kV range v of electron 70% of speed of light, thus relativistic

expression of energy: for 200kV λ≈2.5pm.

Intensity of the diffracted beam:

$$I_{\mathbf{g}} = \left| \psi_{\mathbf{g}} \right|^2 \propto \left| F_{\mathbf{g}} \right|^2 \hspace{0.5cm} F_{\mathbf{g}} = \sum f_i e^{-2\pi i \mathbf{g} \cdot \mathbf{r}_i}$$

where F_{α} is the structure factor and g is the scattering vector.

Advantages of electron diffraction

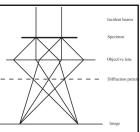
- Wave length is smaller than for X-ray (100pm).
- Geometry of diffraction experiment can be varied by electron lenses.
- Diffraction on nanoscale single crystal is possible
- Can be combined with direct image of the crystal, EDS, EELS or electron holography.

Good for symmetry determination, not so accurate to get lattice parameters Si nanowire. The inset is a selected area electron

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diffraction pattern of the nanowire.

Nanotechnology and material science Lecture IV Applied Physics Letters 83, 2934 (2003)



(Up) The objective lens acts to collect all electrons (op) The objective lens acts to collect an electrons scattered from one point of the sample in one point on the fluorescent screen, resulting an image of the sample.

Note that at the dashed line in the figure, electrons scattered in the same direction by the sample are collected into a single point. This is the back focal plane., and is where the diffraction pattern is formed. By manipulating the magnetic lenses the position of focal plane can be varied.

